

**WHAT IS CLAIMED IS:**

1. A manufacturing apparatus comprising:
  - a loading chamber;
  - 5 a transporting chamber coupled to the loading chamber;
  - a plurality of film formation chambers coupled to the transporting chamber;
  - a processing chamber coupled to the transporting chamber;
  - wherein each of the plurality of film formation chambers is coupled to a vacuum evacuation processing chamber for making the inside of the film formation
  - 10 chamber vacuum;
  - wherein each of the plurality of film formation chambers comprises:
    - an alignment means for performing a position alignment of a mask and a substrate;
    - a substrate holding means;
    - 15 an evaporation source holder; and
    - a means for moving the evaporation source holder;
    - wherein the evaporation source holder comprises:
      - a container that seals an evaporation material;
      - a means for heating the container; and
      - 20 a shutter formed over the container;
    - wherein the processing chamber is coupled to a vacuum evacuation processing chamber for providing a vacuum state,
    - wherein a plurality of plate heaters are disposed within the processing chamber so as to overlap and open gaps therebetween, and
    - 25 wherein the processing chamber can perform vacuum heating on a plurality of substrates.

2. A manufacturing apparatus according to claim 1, wherein a means for moving the evaporation source holder functions to move the evaporation source

holder in an x-axis direction at a certain pitch, and functions to move the evaporation source holder in a y-axis direction at a certain pitch.

3. A manufacturing apparatus according to claim 1, wherein the evaporation  
5 source holder is rotated when switching between the x-axis direction and the y-axis direction.

4. A manufacturing apparatus according to claim 1, wherein a hole of an  
opening surface area S2, which is smaller than an opening surface area S1 of the  
10 container, is opened in the shutter.

5. A manufacturing apparatus according to claim 1, wherein a film  
thickness monitor is formed adjacent to the evaporation source holder.

15 6. A manufacturing apparatus according to claim 1, wherein the inert gas  
element comprises at least one selected from the group consisting of He, Ne, Ar, Kr,  
and Xe.

7. A manufacturing apparatus comprising:  
20 a loading chamber;  
a transporting chamber coupled to the loading chamber;  
a plurality of film formation chambers coupled to the transporting chamber;  
a processing chamber coupled to the transporting chamber;  
wherein each of the plurality of film formation chambers is coupled to a  
25 vacuum evacuation processing chamber for making the inside of the film formation  
chamber vacuum;  
wherein each of the plurality of film formation chambers comprises:  
an alignment means for performing position alignment of a mask  
and a substrate;

a substrate holding means;  
an evaporation source holder; and  
a means for moving the evaporation source holder;  
wherein the evaporation source holder comprises:  
5 a container that seals an evaporation material;  
a means for heating the container; and  
a shutter formed over the container;  
wherein the processing chamber is coupled to a vacuum evacuation  
processing chamber for providing a vacuum state, and  
10 wherein at least one of a hydrogen gas, an oxygen gas, and an inert gas is  
introduced in the processing chamber to generate a plasma.

8. A manufacturing apparatus according to claim 7, wherein a plurality of  
plate heaters are disposed in the transporting chamber so as to overlap and open  
15 gaps therebetween and a processing chamber capable of performing vacuum heating  
on a plurality of substrates is coupled to the transporting chamber.

9. A manufacturing apparatus according to claim 7, wherein a means for  
moving the evaporation source holder functions to move the evaporation source  
20 holder in an x-axis direction at a certain pitch, and functions to move the  
evaporation source holder in a y-axis direction at a certain pitch.

10. A manufacturing apparatus according to claim 7, wherein the  
evaporation source holder is rotated when switching between the x-axis direction  
25 and the y-axis direction.

11. A manufacturing apparatus according to claim 7, wherein a hole of an  
opening surface area S2, which is smaller than an opening surface area S1 of the  
container, is opened in the shutter.

12. A manufacturing apparatus according to claim 7, wherein a film thickness monitor is formed adjacent to the evaporation source holder.

5           13. A manufacturing apparatus according to claim 7, wherein the inert gas element comprises at least one selected from the group consisting of He, Ne, Ar, Kr, and Xe.